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Towards High Efficiency Industrial FEL

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Industrial Lasers

 Industrial lasers play critical role in modern manufacturing, materials processing, printing, and other high throughput industrial processes



- \$3.5 billion industry in 2017
- \$1.3 billion micro-materials segment (semiconductor industry, fine materials processing) represents high added value applications and is rapidly growing (~20% year over year)

Revenues by sector	2015	2016 est.	2017 proj.
Marking	\$ 543	\$ 560	\$ 569
Marco-materials	\$ 1,428	\$1,492	\$ 1,565
Micro-materials	\$895	\$ 1,105	\$ 1,299
Total	\$ 2,866	\$ 3,157	\$ 3,432

http://www.industrial-lasers.com/articles/print/volume-32/issue-1/features/industrial-lasers-continue-solid-revenue-growth-in-2016.html

Industrial Applications

- FEL technology is unique due to its scalability to any desired operating wavelength from THz to X-rays
- At shorter wavelengths (< 100 nm), outside the range of state-of-theart industrial lasers, FEL can fulfill the needs of growing micromaterial processing segment
- Semiconductor industry HVM offers a prime example of high added value application (EUV lithography), where there is a demand for short wavelengths light sources on a massive scale
- EUVL light source at 13.5 nm illustrates FEL industrial potential



EUVL challenge

- EUVL process implies ultraprecise projection of the mask image on wafer in a high throughput setting (>120 wph per scanner)
- Reflective optics at EUV are far from perfect (R < 70%), so high power EUV light source is required (250 W in the intermediate focus).
- Development of high power laser produced plasma (LPP) source was a monumental effort, and only recently achieved 250 W target
- LPP is expensive (~\$100 million per scanner w/10-20 scanners per foundry, plus high operating cost)



Courtesy of P. Naulleau (LBNL)

Possibility for FEL EUVL source

- FEL @ 13.5 nm in theory has a number of advantages compare to LPP:
 - No media, no heat and no contamination
 - Scalable to non-granular design (one source per foundry instead of one source per scanner)
 - Consistent with the cost and scale of the modern foundry facilities
- To compete with LPP, FEL have to offer significant cost advantages, to compensate the risks associated with the new technology





Courtesy of P. Naulleau (LBNL)

Industrial FEL

- Industrial applications require improvements to the FEL cost efficiency by 1-2 orders of magnitude
- One approach is beam energy recuperation (SCRF CW + ERL)
- Another approach is a major improvement to FEL efficiency

FEL efficiency: lessons from Inverse FEL

- In a conventional SASE FEL the electronsphotons energy exchange rate peaks (near saturation) at about ~ 1 MeV/m
- UCLA experiment on RUBICON IFEL achieved ~ 100 MeV/m acceleration
- In IFEL, e-beam and laser exchange energy in vacuum, thus the process is reversible
- 100 MeV/m in-vacuum decelerator would make a very efficient radiator, so can we design FEL which operates as IFEL in reverse?
- IFEL experiments demonstrated that strong energy exchange and very high efficiency FEL schemes <u>are possible</u> within the state of the art technological framework



In an IFEL the electron beam absorbs energy from a radiation field.



UCLA results from RUBICON experiments J. Duris et al, *Nature Comm.* **5**, 4928, 2014

TESSA

- Inverse IFEL = TESSA (Tapering Enhanced <u>Stimulated</u> Superradiant Amplification)
- Requires seed pulse of high intensity (larger than P_{SAT})
- Tapering is optimized using GIT algorithm (Genesis Informed Tapering) developed at UCLA for IFEL



TESSA at **EUV**

- GIT simulations of TESSA at EUV
- E-beam decelerates from 1 GeV to 320 MeV in 23 m undulator,
- Laser power increases from ~ 5 GW seed to > 1 TW at the output
- W/capture ~ 80%, the overall energy efficiency > 50% is possible
- Sensitive to peak current (4 kA for this working point, may not be easy to achieve at 1 GeV energy)
- **5** GW seed does not exist (but can be generated by refocusing SASE or in an oscillator)



TESSA proof-of-concept experiment

- Numerical studies at 13.5 nm are very promising
- Pilot experimental test was carried out by UCLA at BNL ATF at 10 μm
- Demonstrated > 30% energy extraction from the electron beam in a 50 cm undulator !





Double buncher experiment

- Double buncher enabled improving IFEL capture to >80%
- Recently demonstrated by N. Sudar et al.



TESSA-266

- So far, TESSA concept has been developed, and demonstrated at 10 μm , including efficient beam capture with the double buncher
- Next goal is to show high gain amplification and study system dynamics and optimization experimentally at a shorter (and friendlier) wavelength (266 nm)



- The site of the experiment is LEA tunnel at Argonne (former LEUTL)
- A thorough design study for TESSA-266 is underway in collaboration with UCLA, Argonne, and RadiaSoft

TESSA-266

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- Start to end simulations are in progress
- The goal is to reach 15% FEL efficiency in 4 meter undulator at 266 nm
- Laser amplification gain > 20

- Strong focusing helical undulator design and optimization is in progress
- Anticipate the start of the construction phase in Summer 2018

TESSA Electron Beam Requirements		
Property	Value	
Energy	$300{ m MeV}$	
Energy Spread	0.02% to $0.1%$	
Peak Current	$1 \mathrm{kA}$	
Emittance (Normalized)	$2\mu{ m m}$	
spot size (rms)	$30\mu{ m m}$ to $40\mu{ m m}$	
$\beta_{x,y}$	$0.54\mathrm{m}$ to $1\mathrm{m}$	



and Chris Hall (RadiaSoft)

Road Map

- Beyond TESSA-266 we have to show high average power and high efficiency oscillator configuration
- Considering the possibility of moving TESSA-266 to Fermilab to demonstrate oscillator regime with SCRF linac
- The ultimate goal is TESSA at EUV in a high duty cycle mode



Conclusions and Acknowledgement

- The advances in FEL and accelerator science and technology open up possibilities for industrial grade systems
- More specifically, a possibility of EUV FEL for semiconductor industry has triggered important discussions about industrial FEL efficiency, reliability and architecture
- TESSA is a novel approach to develop very high efficiency FEL, and experimental validation is in progress
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• See MOP011, TUP022, TUP052, WEP079 papers for more details